L Number	Hits	Search Text	DB	Time stamp
1	7136	(SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 18:54
2	3883	((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
3	626	(((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 19:25
4	70	dimension\$4) ((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:25
5	7	<pre>width) ((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:56
6	7	<pre>((((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:57
7	7	<pre>((((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 18:57
9	4	<pre>(((((((((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) hear2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4))) and (correct\$4 with (dos\$4</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
10	2	or exposure)) ((((((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4)) and model\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
12	4		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18

Search History 11/18/03 7:27:57 PM Page 1

13	1	((((((((SEM or (scanning adj electron	USPAT;	2003/11/18
		adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	19:07
8	7	<pre>width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4))) and ((correct\$4 or compensat\$5) with (dos\$4 or exposure))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:08
		or determin\$5 or measur\$6) with (chang\$4 or bias\$4))		
11	7	((((((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and (edge near2 bias\$4)) and focus\$4) and patterns) and ((calculat\$5 or determin\$5 or measur\$6) with (chang\$4 or bias\$4)) and reference	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:08
14	1545		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
15	278	<pre>((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and (electron with imag\$5)) and ((critical\$4 or characteristic) near2 dimension\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
16	36		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:27
17	33	((((((SEM or (scanning adj electron adj microscop\$3)) and electron and (resist or photoresist)) and imag\$5) and (electron with imag\$5)) and ((critical\$4 or characteristic) near2 dimension\$4)) and ((edge or pattern) near width)) and monitor\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:27

L Number	Hits	Search Text	DB	Time stamp
18	12771	(SEM or (scanning adj electron adj microscop\$4)) and monitor\$4	USPAT; US-PGPUB; EPO; JPO;	2003/11/18 19:29
19	1407	((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2003/11/18 19:29
20	171	(((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)	DERWENT; IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
21	158	((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 19:30
22	21	and pattern (((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4) or characteristic\$4) near2 dimension\$4))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
23	14	and pattern) and (edge near2 width) ((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
24	9	<pre>(critical\$4 or characteristic)) (((((((SEM or (scanning adj electron adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4 or characteristic\$4) near2 dimension\$4)) and pattern) and (edge near2 width)) and ((calculat\$5 or determin\$4) near6 (critical\$4 or characteristic))) and ((calculat\$4 or determin\$4) near5 (exposure or dos\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:34
26	5		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 19:35

		[TICD TO	2002/11/10
27	٥	((((((((SEM or (scanning adj electron	USPAT; US-PGPUB;	2003/11/18
1		<pre>adj microscop\$4)) and monitor\$4) and (electron near5 imag\$5)) and ((critical\$4</pre>	EPO; JPO;	19.00
			DERWENT;	
1 1		or characteristic\$4) near2 dimension\$4))	,	
		and pattern) and (edge near2 width)) and	IBM_TDB	
,)		((calculat\$5 or determin\$4) near6	}	j l
[i		(critical\$4 or characteristic))) and	'	1
1		((calculat\$4 or determin\$4) near5		
1 1		(exposure or dos\$4))) and (((((((SEM or	[
		(scanning adj electron adj microscop\$4))		
ſ	1	and monitor\$4) and (electron near5	į	[
1		imag\$5)) and ((critical\$4 or		i
ł		characteristic\$4) near2 dimension\$4)) and	1	1
1		pattern) and (edge near2 width)) and		ĺ
ł		((calculat\$5 or determin\$4) near6	}	
		(critical\$4 or characteristic))) and		
ļ		model\$4)) and correct\$5]	}
28	5	(((((((((SEM or (scanning adj electron	USPAT;	2003/11/18
1 40	٠ - ١	adj microscop\$4)) and monitor\$4) and	US-PGPUB;	19:51
			1	1 19.31
j l		(electron near5 imag\$5)) and ((critical\$4	EPO; JPO;	j
		or characteristic\$4) near2 dimension\$4))	DERWENT;	
]	and pattern) and (edge near2 width)) and	IBM_TDB	
1	[((calculat\$5 or determin\$4) near6	1	
		(critical\$4 or characteristic))) and		
]	{	((calculat\$4 or determin\$4) near5	ĺ	
		(exposure or dos\$4))) and (((((((SEM or		
	•	(scanning adj electron adj microscop\$4))		l l
		and monitor\$4) and (electron near5		
		imag\$5)) and ((critical\$4 or	ł	
		characteristic\$4) near2 dimension\$4)) and		
}		pattern) and (edge near2 width)) and	1	<u> </u>
		((calculat\$5 or determin\$4) near6		
		(critical\$4 or characteristic))) and	}]
		model\$4)) and correct\$5) and width		
25	10	((((((SEM or (scanning ad) electron ad)	USPAT;	2003/11/18
		microscop\$4)) and monitor\$4) and	US-PGPUB;	19:50
]]	(electron near5 imag\$5)) and ((critical\$4	EPO; JPO;]
		or characteristic\$4) near2 dimension\$4))	DERWENT;	
		and pattern) and (edge near2 width)) and	IBM TDB	
[1		((calculat\$5 or determin\$4) near6		
		(critical\$4 or characteristic))) and		
]			1	1
	_	model\$4	HCDAT.	2003/11/19
29	5	(((((((SEM or (scanning adj electron adj	USPAT;	2003/11/18
	!	microscop\$4)) and monitor\$4) and	US-PGPUB;	19:49
]		(electron near5 imag\$5)) and ((critical\$4	EPO; JPO;	
		or characteristic\$4) near2 dimension\$4))	DERWENT;	1
) .]	and pattern) and (edge near2 width)) and	IBM_TDB]
1 1		((calculat\$5 or determin\$4) near6		1
<u>j</u>		(critical\$4 or characteristic))) and		J
1		((calculat\$4 or determin\$4) near5		1
		(exposure or dos\$4))) and model\$4		
30	10	(((((((SEM or (scanning adj electron adj	USPAT;	2003/11/18
		microscop\$4)) and monitor\$4) and	US-PGPUB;	19:50
į :		(electron near5 imag\$5)) and ((critical\$4	EPO; JPO;	1
1		or characteristic\$4) near2 dimension\$4))	DERWENT;	
		and pattern) and (edge near2 width)) and	IBM TDB	ì
]		((calculat\$5 or determin\$4) near6	_	
[]		(critical\$4 or characteristic))) and	1	1
		model\$4) and correct\$5	1	
31	10	((((((((SEM or (scanning adj electron	USPAT;	2003/11/18
31	10	adj microscop\$4)) and monitor\$4) and	US-PGPUB;	19:53
])	(electron near5 imag\$5)) and ((critical\$4)	EPO; JPO;	1
		or characteristic\$4) near2 dimension\$4))	DERWENT;	
]]	and pattern) and (edge near2 width)) and	IBM TDB	}
			TBPI_IDB	
1		((calculat\$5 or determin\$4) near6		
[!		(critical\$4 or characteristic))) and model\$4) and correct\$5) and width		[
		I MODELS 4 I SDO CORRECTS 5 I SDO MIDTE	1	1

L Number	Hits	Search Text	DB	Time stamp
41	15192	(electron adj beam) and lithograph\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18 21:05
42	79	((electron adj beam) and lithograph\$3) and (edge near width)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 21:11
43	27	<pre>(((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
44	16	<pre>((((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 21:11
45	12	(((((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
46	11	<pre>(((((((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
47	3	<pre>(((((((electron adj beam) and lithograph\$3) and (edge near width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and (exposure near2 energ\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
48	168	((electron adj beam) and lithograph\$3) and (edge near2 width)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 21:11
49	55	(((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 21:11
50	31	<pre>((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:17
51	16	(((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
52	14	<pre>((((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12

		, , , , , , , , , , , , , , , , , , , 		1 0 0 0 2 / 1 1 / 1 0
53	3	<pre>(((((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and (exposure near2 energ\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:12
54	3	<pre>(((((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and ((exposure or dos\$4) near2 energ\$4)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18
55	2	(((((((electron adj beam) and lithograph\$3) and (edge near2 width)) and ((calculat\$5 or determin\$4) with (dimension\$4))) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$4) with (bias\$4 or deviat\$4))) and focus\$4) and ((exposure or dos\$4) near2 energ\$4)) and correct\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:14
56	43036	imag\$5 with electron	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
57	5735	(imag\$5 with electron) and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
58	4907	((imag\$5 with electron) and (resist or photoresist)) and pattern\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 21:15
59	87	<pre>(((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18
60	74	<pre>((((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 21:17
61	39	<pre>(((((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge) and ((second or test or reference) near (pattern or portion))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 21:18
62	9	((((((imag\$5 with electron) and (resist or photoresist)) and pattern\$4) and ((calculat\$5 or determin\$4) near5 ((characteristic or critical) near2 dimension\$3))) and width and edge) and ((second or test or reference) near (pattern or portion))) and ((calculat\$5 or determin\$5) with (change or deviation or bias\$4) with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18

64	4	(((((((imag\$5 with electron) and (resist	USPAT;	2003/11/18
ĺ	Į l	or photoresist)) and pattern\$4) and	US-PGPUB;	21:21
i		((calculat\$5 or determin\$4) near5	EPO; JPO;	
ł .	1	((characteristic or critical) near2	DERWENT;	{
1	1	dimension\$3))) and width and edge) and	IBM_TDB	}
]]	((second or test or reference) near]
,	((pattern or portion))) and ((calculat\$5		
		or determin\$5) with (change or deviation		
ĺ	1	or bias\$4) with exposure)) and (correct\$4		
		with exposure)) and model\$4		
63	6	((((((imag\$5 with electron) and (resist	USPAT;	2003/11/18
	1	or photoresist)) and pattern\$4) and	US-PGPUB;	21:21
l	1	((calculat\$5 or determin\$4) near5	EPO; JPO;	
		((characteristic or critical) near2	DERWENT;	ļ
		dimension(3))) and width and edge) and	IBM_TDB	
		((second or test or reference) near		ľ
ĺ	1	(pattern or portion))) and ((calculat\$5]
1		or determin\$5) with (change or deviation		
		or bias\$4) with exposure)) and (correct\$4		
	1	with exposure)	L	ll

L	Hits	Search Text	DB	Time stamp
Number 1	12065	imag\$5 near2 electron	USPAT;	2003/11/18
-			US-PGPUB;	22:17
			EPO; JPO;	
			DERWENT; IBM TDB	
2	2908	(imag\$5 near2 electron) and (resist or	USPĀT;	2003/11/18
		photoresist or mask or photomask)	US-PGPUB;	22:18
			EPO; JPO;	
			DERWENT; IBM TDB	
3	165	((imag\$5 near2 electron) and (resist or	USPAT;	2003/11/18
		photoresist or mask or photomask)) and	US-PGPUB;	22:19
1		((characteristic or critical) near	EPO; JPO;	
1		dimension\$4)	DERWENT; IBM TDB	
4	106	(((imag\$5 near2 electron) and (resist or	USPAT;	2003/11/18
1		photoresist or mask or photomask)) and	US-PGPUB;	22:20
1		((characteristic or critical) near	EPO; JPO;	
1		dimension\$4)) and (edge and width or (edge-width))	DERWENT; IBM TDB	
5	34	((((imag\$5 near2 electron) and (resist or	USPAT;	2003/11/18
		photoresist or mask or photomask)) and	US-PGPUB;	22:35
		((characteristic or critical) near	EPO; JPO;	
1		dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern	DERWENT; IBM TDB	
1		or portion or area))		
6	16	(((((imag\$5 near2 electron) and (resist	USPAT;	2003/11/18
1		or photoresist or mask or photomask)) and ((characteristic or critical) near	US-PGPUB; EPO; JPO;	22:24
1		dimension\$4)) and (edge and width or	DERWENT;	
1		(edge-width))) and (second near2 (pattern	IBM_TDB	
1		or portion or area))) and ((calculat\$5 or		
7	16	<pre>determin\$5) with (deviat\$4 or bias\$4)) ((((((imag\$5 near2 electron) and (resist</pre>	USPAT;	2003/11/18
, <i>'</i>	10	or photoresist or mask or photomask)) and	US-PGPUB;	22:25
1		((characteristic or critical) near	EPO; JPO;	
1		dimension\$4)) and (edge and width or	DERWENT;	
1		<pre>(edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or</pre>	IBM_TDB	
1		determin\$5) with (deviat\$4 or bias\$4)))]
1		and energ\$4		1
8	2	(((((((imag\$5 near2 electron) and (resist	USPAT; US-PGPUB;	2003/11/18
		or photoresist or mask or photomask)) and ((characteristic or critical) near	EPO; JPO;	22:26
		dimension\$4)) and (edge and width or	DERWENT;	
		(edge-width))) and (second near2 (pattern	IBM_TDB	
		or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4)))		
		and energ\$4) and (correct\$4 with		
,		(exposure or energ\$4 or dos\$4))		
9	15	(((((((imag\$5 near2 electron) and (resist	USPAT;	2003/11/18
		or photoresist or mask or photomask)) and ((characteristic or critical) near	US-PGPUB; EPO; JPO;	22:26
,		dimension\$4)) and (edge and width or	DERWENT;	
,		(edge-width))) and (second near2 (pattern	IBM_TDB	
	İ	or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4)))		
		and energ\$4) and (correct\$4 and (exposure		
,		or dos\$4))		
10	15	(((((((imag\$5 near2 electron) and	USPAT;	2003/11/18
		<pre>(resist or photoresist or mask or photomask)) and ((characteristic or</pre>	US-PGPUB; EPO; JPO;	22:27
,		critical) near dimension\$4)) and (edge	DERWENT;	
,		and width or (edge-width))) and (second	IBM_TDB	
,		near2 (pattern or portion or area))) and	1	}
,		((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4))) and energ\$4) and		
		(correct\$4 and (exposure or dos\$4))) and	1	
		(model\$4 or reference or librar\$4 or		
		simulat\$5)	<u> </u>	<u> </u>

11	15	<pre>((((((((((imag\$5 near2 electron) and (resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:32
12	3	<pre>(resist or photoresist or mask or photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 22:30
13	2	(resist or photoresist or mask or	USPAT; US-PGPUB;	2003/11/18 22:36
		photomask)) and ((characteristic or critical) near dimension\$4)) and (edge and width or (edge-width))) and (second near2 (pattern or portion or area))) and ((calculat\$5 or determin\$5) with (deviat\$4 or bias\$4)) and energ\$4) and (correct\$4 and (exposure or dos\$4))) and (model\$4 or reference or librar\$4 or simulat\$5)) and focus\$4) and (calculat\$4 with (deviat\$4 or bias\$4) with focus)	EPO; JPO; DERWENT; IBM_TDB	
14	360	1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:35
15	49	((calculat\$4 with (dimension\$3 near (characteristic or critical)))) and (second near (pattern or portion or area))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:36
16	4	<pre>(((calculat\$4 with (dimension\$3 near (characteristic or critical)))) and (second near (pattern or portion or area))) and ((calculat\$4 or determin\$5) with (deviat\$4 or bias\$4) with focus)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:39
17	4		USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:43
18	3160	((calculat\$4 or blas\$4); with locus) ((calculat\$4 or determin\$5) with (change or deviat\$4 or blas\$4) with exposure)	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/18
19	1191	((calculat\$4) with (change or deviat\$4 or bias\$4) with exposure)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:55
20	1260	<pre>(((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/11/18 22:56

-	1007	1/// 3 3 3 3 4 4 3 4 4 5 5 5 5 5 5 5 5 5 5 5	TTODAM	1 2002 /11 /10
21	1087	((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
		(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:56
		exposure)) and ((correct\$4 or	EPO; JPO;	
		compensat\$5) with exposure)) and (model\$4	DERWENT;	[
		or reference)	IBM_TDB	
22	214	((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
Í		(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:57
		exposure)) and ((correct\$4 or	EPO; JPO;	
	!	compensat\$5) with exposure)) and	DERWENT;	
	1	(model\$4)	IBM TDB	ľ
23	250	(((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
23	200	(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:58
		exposure)) and ((correct\$4 or	EPO; JPO;	
		compensat\$5) with exposure)) and (model\$4	DERWENT;	
				ļ
	1	or reference)) and ((second or test or	IBM_TDB	1
		reference) near (pattern or portion))	uan na	2002/11/10
24	20	((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
!	}	(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:59
		exposure)) and ((correct\$4 or	EPO; JPO;	ļ
		compensat\$5) with exposure)) and (model\$4	DERWENT;]
}	1	or reference)) and ((second or test or	IBM_TDB	1
		reference) near (pattern or portion)))		
]	and (calculat\$5 near4 dimension\$3)		
25	16	((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
		(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:59
		exposure)) and ((correct\$4 or	EPO; JPO;	
	}	compensat\$5) with exposure)) and (model\$4	DERWENT;	}
		or reference)) and ((second or test or	IBM TDB	l
		reference) near (pattern or portion)))	1211_122	
1		and (calculat\$5 near4 dimension\$3)) and		}
		electron		
1 2 6	1.0		1100000	2003/11/18
26	16		USPAT;	22:59
		(change or deviat\$4 or bias\$4) with	US-PGPUB;	22:39
		exposure)) and ((correct\$4 or	EPO; JPO;	l
		compensat\$5) with exposure)) and (model\$4	DERWENT;	}
		or reference)) and ((second or test or	IBM_TDB	Į į
		reference) near (pattern or portion)))		
l		and (calculat\$5 near4 dimension\$3)) and		!
		electron) and pattern		
27	14	((((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
		(change or deviat\$4 or bias\$4) with	US-PGPUB;	23:00
		exposure)) and ((correct\$4 or	EPO; JPO;	
	Ì	compensat\$5) with exposure)) and (model\$4	DERWENT;	
		or reference)) and ((second or test or	IBM TDB]
		reference) near (pattern or portion)))	_	
		and (calculat\$5 near4 dimension\$3)) and	1	
		electron) and pattern) and width	}	
28	5	(((((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
20	ا آ	(change or deviat\$4 or bias\$4) with	US-PGPUB;	23:03
]			EPO; JPO;	23.00
		<pre>exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4</pre>		
			DERWENT;]
		or reference)) and ((second or test or	IBM_TDB	Į .
		reference) near (pattern or portion)))		
		and (calculat\$5 near4 dimension\$3)) and		
]	electron) and pattern) and width) and	J	Į .
		(electron near5 imag\$5)		
29	5	((((((((((calculat\$4 or determin\$5) with	USPAT;	2003/11/18
]	(change or deviat\$4 or bias\$4) with	US-PGPUB;	23:03
		exposure)) and ((correct\$4 or	EPO; JPO;	
		compensat\$5) with exposure)) and (model\$4	DERWENT;	1
]	or reference)) and ((second or test or	IBM_TDB	Į .
		reference) near (pattern or portion)))	_	
		and (calculat\$5 near4 dimension\$3)) and		
]]	electron) and pattern) and width) and	ļ	1
		(electron near5 imag\$5)) and (resist or		
		photoresist)		
		<u></u>		·

30	3	<pre>((((((((((((((((((((((((((((((((((((</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:05
31	5	<pre>(((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:08
32	3	<pre>((((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and observ\$6</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:06
34	4	(((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference)) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process) and ((characteristic or critical\$3) near dimension\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:09
33	5	<pre>(((((((((((((calculat\$4 or determin\$5) with (change or deviat\$4 or bias\$4) with exposure)) and ((correct\$4 or compensat\$5) with exposure)) and (model\$4 or reference) and ((second or test or reference) near (pattern or portion))) and (calculat\$5 near4 dimension\$3)) and electron) and pattern) and width) and (electron near5 imag\$5)) and (resist or photoresist)) and process) and (characteristic or critical\$3)</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/11/18 23:26